

Focused Ion Beam (FIB 200) FEI

A Focused Ion Beam (FIB) instrument uses a finely focused ion beam to raster over the sample surface for imaging or precise sputtering and modification of the sample. In conjunction with gas-injection systems, ion beam assisted deposition of metals or insulators and enhanced etching of selected materials are possible. System was used in a lab environment and decommissioned by FEI.

Inclusive:

Operating system (PC and electronics in table)

Pelco nPMC14F

Keithley 485

Toyo TP-6530 printer

Leader LBO-51MA

Console



FIB model	FIB 200XP Single Beam
Accelerating Voltage	30kV
Resolution	Ion Beam -5nm at 30kV
Probe current	1pA~11.5nA
Detector	CDEM
Gas Source	<ul style="list-style-type: none">• Platinum• TEOS• Enhanced etch• Delineation etch

